



### Relative Sputter Factors

KV	Area (mm)	Rate (A/Sec) (Base on SiO <sub>2</sub> )
0.5	1X1	No Data
0.5	2X2	0.25 (surface clean use 12s treatment)
0.5	4x4	No Data
1	1X1	No Data
1	2X2	0.5
1	4x4	No Data
2	1X1	No Data
2	2X2	1
2	4x4	No Data
3	1X1	No Data
3	2X2	1.5
3	4x4	No Data
4	1X1	No Data
4	2X2	2
4	4x4	No Data
5	MAX	No Data

Material	Relative Sputter Factor
SiO <sub>2</sub>	1.00
Si <sub>3</sub> N <sub>4</sub>	0.75
Al	1.12
Al <sub>2</sub> O <sub>3</sub>	0.5
Al <sub>0.3</sub> GaAs	1.2
Ta	0.12
Ta <sub>2</sub> O <sub>5</sub>	1.18
TaN	0.4
Ti	0.58
TiO <sub>2</sub>	0.75
TiN	0.28-0.37
Au	1.3 (varies widely)
Co	0.64
Cr	0.4
Cu	0.56
GaAs	1.3
Mo	0.6
W	0.4
C doped 52100 steel	0.23
Diamond-like C (DLC)	0.25
Mg	0.4

Material rate = SiO<sub>2</sub> rate x RSF (relative sputter factor)